



SHEET 1 OF 1

INFORMATION DISCLOSURE  
CITATION IN AN  
APPLICATION

(PTO-1449)

ATTY. DOCKET NO.  
**055071-0351**SERIAL NO.  
**10/813,626**APPLICANT  
**Robert SOCHA**FILING DATE  
**March 31, 2004**GROUP  
**4750 2851**

## U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code <sup>2</sup> (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
MB ↓		US 5,680,588	10-21-1997	Gortych et al.	
		US 5,300,788	04-05-1994	Brunner et al.	
		US 5,805,290	09-08-1998	Ausschnitt et al.	
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## FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Code <sup>1</sup> -Number <sup>1</sup> -Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation	
						Yes	No
		<del>JP 2000-222067A</del>				X	

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
		<del>BURN J. LIN, "The Exposure-Defocus Forest," Jpn. J. Appl. Phys. Vol. 33 (1994), pp. 6758-6764</del>
		<del>M. DUSA et al., "Study of mask aerial images to predict CD proximity and line end shortening of resist patterns," Proc. of SPIE Vol. 4349 (2001), pp. 148-159</del>
		<del>B.P. MATHUR et al., "Quantitative Evaluation of Shape of Image on Photoresist of Square Apertures," IEEE Transactions of Electron Devices, Vol. 35, No. 3 (March 1988), pp. 294-297</del>
		<del>CHRISTOPHER J. PROGLER et al., "Merit functions for lithographic lens design," J. Vac. Sci. Technol. B 14(6), (Nov/Dec 1996), pp. 3714-3718</del>
		<del>NISHRIN KACHWALA et al., "Imaging contrast improvement for 160 nm line features using sub resolution assist features with binary, 6% ternary attenuated phase shift mask with process tuned resist," SPIE Vol. 3879 (1999), pp. 55-67</del>

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9/19/07

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.

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[illegible]

FOREIGN PATENT DOCUMENTS

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						Yes	No
MF		WO 98/40791	09/17/1998	Konin Klijke Philips Electronics N.V.		X	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.

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